

ACKNOWLEDGEMENT RECEIPT

Electronic Version 1.1

Stylesheet Version v1.1.1

Title of Invention

Method for forming silicon dioxide film using siloxane

Submission Type : Information Disclosure
Statement

Application Number:

10/782094



EFS ID:

77283

Server Response:

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First Named Applicant: Jae-Eun Park

Attorney Docket Number: SAM-0483

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File Listing:

Doc. Name	File Name	Size (Bytes)	Date Produced (yyyymmdd)
us-ids	SamsungFourEightyThreePartTwo-usidst.xml	953	2005-02-02
us-ids	us-ids.dtd	7763	2005-02-02
us-ids	us-ids.xsl	12026	2005-02-02
package-data	SamsungFourEightyThreePartTwo-pkda.xml	2053	2005-02-02
package-data	package-data.dtd	27025	2005-02-02
package-data	us-package-data.xsl	19263	2005-02-02
Total files size		69083	

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